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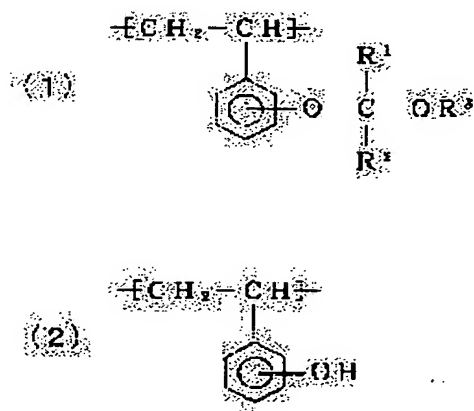
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(54) BASE RESIN FOR POSITIVE TYPE RESIST

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a new base resin for a positive type resist giving a radiation sensitive chemical amplification type positive resist composition having high sensitivity and high resolution, ensuring good heat resistance, good focal depth-width characteristics, good aging stability relating to pattern form and good shelf stability of a resist solution and capable of forming a resist pattern having no substrate dependency and excellent in profile shape.

SOLUTION: The base resin comprises a poly(hydroxystyrene) derivative consisting of 10-60 mol% constitutional units of formula (1) (where R¹ is H or methyl; R² is methyl or ethyl; and R³ is a 1-4C lower alkyl) and 90-40 mol% constitutional units of formula (2) and having a weight average molecular weight of 8,000-25,000 and a molecular weight distribution (Mw/Mn) of ≤ 1.5.



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